

# Citations for Ion : Bi

<b>Pub. Year</b>	<b>Authors, Title, Journal Citation and Comments</b>	<b>Citation Numb</b>
<b>1966</b>	Nielsen, O <b>'Specialeopgave'</b> <i>Niels Bohr Institute, University of Copenhagen, Pp. 1-64 (1966)</i> Comment : S, dS. 50 keV C, Na, Cl, K, Mn, Y, Zn, Ag, Hf, Lu, Hg, Bi -> H2, D2, He, N2, Ne, Ar	1966-Niel
<b>1970</b>	Eldridge, G. Govind, P. K. Nieman, D. A. Chernow, F. <b>'Radiation Damage Studies of Bismuth Ion-Implanted CdS'</b> <i>Proc. of the European Conference on Ion Implantation. Peter Peregrinus, Publisher, Stevenhage, England, P. 143-48 (1970)</i> Comment : R, dR. 25 keV Bi -> CdS	1970-Eldr
<b>1971</b>	Sigurd, D. Domeij, B. <b>'Critical Angles of Sb and Bi Implanted Si'</b> <i>Phys. Letters, 36A, 81-82 (1971)</i> Comment : R. 40 keV Sb, Bi -> Si ([111], [110], [100])	1971-Sigu
<b>1973</b>	Eldridge, G. Chernow, F. Rise, G. <b>'Further Studies of Bismuth-Implanted Cadmium Sulfide'</b> <i>J. Appl. Phys., 44, 3858-61 (1973)</i> Comment : R,dR. 25 keV 209Bi -> CdS (Cryst.)	1973-Eldr
<b>1974</b>	Grant, W. A. Williams, J. S. Dodds, D. <b>'Measurement of Projected and Lateral Range Parameters for Low Energy Heavy Ions in Silicon by Rutherford Backscattering'</b> <i>Meyer, G. Linker and F. Kappeler (Ed.):Ion Beam Surface Layer Analysis, Plenum, N. Y., P. 235-44 (1974)</i> Comment : R, dR, dR(Lateral). 10-80 keV Pb, 50-400 keV Bi, 40 keV Ar, Cu, Kr, Cd, Al, Dy, W -> Si	1974-Gran
<b>1975</b>	Williams, J. S. Grant, W. A. <b>'High Resolution Rutherford Backscattering and Its Application to Ion Range and Ion Collectionrad'</b> <i>Rad. Effects, 25, 55-56 (1975)</i> Comment : R, dR. 20-80 keV Kr, Xe, Cs, Dy, Au, Pb, Bi -> Si, Al	1975-Will
<b>1976</b>	Callaghan, P. T. Kittel, P. Stone, N. J. Johnson, P. D. <b>'Impurity-Site Distribution of Implanted Bi in Iron and Nickel Studied by Channeling and Nuclear Orientation'</b> <i>Phys. Rev. B, 14, 3722-31 (1976)</i> Comment : R, dR, 200 keV Bi -> Fe, Ni (Cryst. Chann. And Random)	1976-Call
<b>1976</b>	Grant, W. A. Williams, J. S. Dodds, D. <b>'Measurement of the Lateral Spread of Heavy Ions Implanted into Silicon'</b> <i>Rad. Effects, 29, 189-90 (1976)</i> Comment : dR(Lateral). (10-40 keV) Cu, Cd, Xe, Dy, Kr, W, Pb, Bi -> Si	1976-Gran3

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<b>1976</b>	Hirvonen, J. K. Hubler, G. K. <b>'Application of a High-Resolution Magnetic Spectrometer to Near-Surface Analysis'</b> <i>Meyer, G. Linker and F. Kappeler (Ed.): Ion Beam Surface Layer Analysis, Plenum, N.Y., P. 457-69 (1976)</i> <i>Comment : R, dR. 2-60 keV 209Bi, 60 keV 69Ga -&gt; Si</i>	<b>1976-Hirv</b>
<b>1976</b>	Sood, D. K. Dearnaley, G. <b>'Ion-Implanted Surface Alloys in Copper and Aluminum'</b> <i>G. Carter, J. S. Colligon, W. A. Grant (Ed.): Appl. of Ion Beams to Materials. Inst. of Physics Conf. Ser. No. 28, 169-203 (1976)</i> <i>Comment : R. (150-300) keV Au, Mo, Bi, Ta, Mo, Gd, Bi, Cu, Rb, Ru, Cs, Ce, Eu, Ag, Cu, Se, Au -&gt; Cu; Rb, Cd, Cs -&gt; Al.</i>	<b>1976-Sood</b>
<b>1979</b>	Santry, D. C. Werner, R. D. Westcott, O. M. <b>'The Range of 120 keV Ions in Solids'</b> <i>IEEE Trans. Nucl. Sci., Ns-26, 1331-1334 (1979)</i> <i>Comment : R, dR. 120 keV Mg, Al, P, S, Cl, K, Ar, Cr, Mn, Cu, Zn, Ga, As, Br, Kr, Rb, Ag, In, Sn, Sb, Te, I, Xe, Cs, Ba, Pr, Au, Hg, Tl, Pb, Bi -&gt; Be, C, Al, Si</i>	<b>1979-Sant</b>
<b>1980</b>	Besenbacher, F. Bottiger, J. Laursen, T. Loftager, P. Moller, W. <b>'Z1-Oscillations in Low-Energy Heavy-Ion Ranges'</b> <i>Nucl. Inst. Methods, 170, 183-188 (1980)</i> <i>Comment : R, dR. Atomic Numbers 18-92 (epsilon=.015) -&gt; Si</i>	<b>1980-Bese2</b>
<b>1980</b>	Kalbitzer, S. Oetzmann, H. <b>'Ranges and Range Theories'</b> <i>Rad. Effects, 47, 57-72, (1980)</i> <i>Comment : R, dR. .1-2 MeV Bi, Sb, As, Ge, P, Au, Cs, Eu, Gd Tb -&gt; Si, Ge, C, Al</i>	<b>1980-Kalb</b>
<b>1982</b>	Geissel, H. Laichter, YI Schneider, W. F. W. Armbruster, P. <b>'Energy Loss and Energy Loss Straggling of Fast Heavy Ions in Matter'</b> <i>Nucl. Inst. Methods, 194, 21-29 (1982)</i> <i>Comment : S. Heavy Ions (18 - 92) at 0.5-10 MeV/amu -&gt; 17 Solids and 5 Gases</i>	<b>1982-Geis</b>
<b>1982</b>	OConnor, D. J. <b>'Accurate RBS Determination of the Range Profile of Implanted Bismuth in Silicon'</b> <i>Nucl. Inst. Methods, 196, 493-497 (1982)</i> <i>Comment : R. Bi (26-120 keV) -&gt; Si</i>	<b>1982-OCon</b>
<b>1985</b>	Behar, M. Fichtner, P. F. Olivieri, C. A. DeSouza, J. P. Zawislak, F. C. <b>'Range Profiles of Implanted Bi and Au in Amorphous Silicon'</b> <i>Nucl. Inst. Methods, B6, 453-458 (1985)</i> <i>Comment : R, dR. Bi, Au (10-390 keV) -&gt; Si</i>	<b>1985-Beha</b>
<b>1985</b>	Fink, D. Biersack, J. P. Chen, J. T. Stadele, M. Tjan, K. <b>'Distributions of Light Ions and Foil Destruction after Irradiation of Organic Polymers'</b> <i>J. Appl. Phys., 58, 668-676 (1985)</i> <i>Comment : R. H, He, Li, B, C, N, Bi (50-300 keV) -&gt; AZ111, PMMA, Epoxy, C, Li, PMCN</i>	<b>1985-Fink</b>

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<b>1985</b>	Geissel, H. Lennard, W. N. Andrews, H. R. Jackson, D. P. Mitchell, I. V. <b>'Energy-Angle Distribution Measurements for 0.8 Vo Ne and Bi Ions Penetrating Thin Carbon Foils'</b> <i>Nucl. Inst. Methods, B12, 38 (1985)</i> Comment : Ne, Bi (20 keV/amu) -> C (angular effects)	<b>1985-Geis</b>
<b>1986</b>	Lennard, W. N. Geissel, H. Jackson, D. P. Phillips, D. <b>'Electronic Stopping Values for Low Velocity Ions (9 &lt;= Z1 &lt;= 92) in Carbon Targets'</b> <i>Nucl. Inst. Methods, B13, 127 (1986)</i> Comment : S. (16 keV/amu) F, Ne, Na, Mg, Al, P, Cl, Ar, K, Sc, Cr, Mn, Cu, Kr, Nb, Ag, In, Xe, Sm, Yb, Au, Bi, U -> C	<b>1986-Lenn2</b>
<b>1987</b>	Grande, P. L. Fichtner, P. F. P. Behar, M. Livi, R. P. Zawislak, F. C. <b>'Projected Ranges and Range Straggling of Au and Bi Implanted into Carbon'</b> <i>Nucl. Inst. Methods, B19/20, 25-27 (1987)</i> Comment : R, dR. Au, Bi (10-400 keV) -> C, SiO <sub>2</sub>	<b>1987-Gran</b>
<b>1988</b>	Guimaraes, R. B. Amaral, L. Behar, M. Zawislak, F. C. Fink, D. <b>'Range Measurements and Thermal Stability Study of AX-111 Photoresist Implanted with Bi Ions'</b> <i>J. Appl. Phys., 63, 2502-2506 (1988)</i> Comment : R, dR. Bi (10-400 keV) -> AZ1111 photoresist	<b>1988-Guim</b>
<b>1988</b>	Wilson, R. G. <b>'(111) Random and (110) Channeling Implantation Profiles and Range Parameters in HgCdTe'</b> <i>J. Appl. Phys., 63, 5302-5311 (1988)</i> Comment : R, dR. 45 Ions (H to Ta) at 100-700 keV -> HgCdTe	<b>1988-Wils</b>
<b>1988</b>	Wilson, R. G. <b>'Ion Implantation and SIMS Profiling of Impurities in II-VI Materials HgCdTe and CdTe'</b> <i>J. Crystal Growth, 86, 735-743 (1988)</i> Comment : R, dR. 52 Ions (H-Hg) at 100-700 keV -> CdTe, HgCdTe	<b>1988-Wils2</b>
<b>1993</b>	Dwivedi, K. K. Kocsis, Z. Varer, P. Brand, R. <b>'Mean Ranges of Bi-209 Ions in ZnP Glass Detector'</b> <i>Nucl. Tracks Rad. Meas. (UK), 22, 47-49 (1993)</i> Comment : S,R. Bi -> ZnP	<b>1993-Dwiv</b>
<b>2000</b>	Weick, H. Geissel, H. Scheidenberger, C. Attallah, F. Cortina, D. <b>'Drastic Enhancement of Energy-Loss Straggling of Relativistic Heavy Ions due to Charge-State Fluctuations'</b> <i>Phys. Rev. Lett., 85, 2725-2728 (2000)</i> Comment : dS. Au, Pb, Bi (100 - 1000 MeV/u) -> Be,Ag,Au,Ta,Pb,Al,Bi,Cu,	<b>2000-Weic</b>

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<b>2000</b>	Weick, H. Geissel, H. Scheidenberger, C. Attallah, F. Baumann, T. <b>'Slowing Down of Relativistic Few-Electron Heavy Ions'</b> <i>Nucl. Inst. Methods, B164-165, 168-179 (2000)</i> <i>Comment : S. Au, Pb, Bi (100 - 1000 MeV/u) -&gt; Be, Al, Cu, Ag, Ta, Au, Pb</i>	<b>2000-Weic2</b>